

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S64	11060	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 14:59
S65	398	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4)) near15 combin\$7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 15:00
S68	2	"4486487".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 15:01
S67	36	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4)) near15 combinat\$7 near15 oxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 15:01
S66	296	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4)) near15 combinat\$7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 15:04
S70	16	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4)) near10 perovskite	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 15:06
S69	16	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4)) near10 (multi\$1compon\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/10 15:06
S71	3	("20030188682" "20040065253").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 14:39
S72	64	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) same superlattice	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 14:45

S73	354	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) near15 ("sio.sub.2" or silicon near2 (dioxide or oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 14:46
S75	16	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) near10 ("sio.sub.2" or silicon near2 (dioxide or oxide)) same "sicl.sub.4"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 14:47
S74	299	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) near10 ("sio.sub.2" or silicon near2 (dioxide or oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 15:44
S77	0	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) near10 ("sio.sub.2" or silicon near2 (dioxide or oxide)) and suntola.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 16:50
S76	29	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) near10 ("sio.sub.2" or silicon near2 (dioxide or oxide)) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 16:50
S78	15	(ale or ald or atomic near2 layer near2 (epitax\$4 or deposit\$4 or process\$4)) and suntola.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 11:56
L1	65	(eva near2 tois suvi near2 haukka marko near2 tuominen).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:05
L3	33	(eva near2 tois suvi near2 haukka marko near2 tuominen).in. and (ald or ale or atomic near2 layer near2 (process\$4 or deposit\$4 or epitax\$5)) near10 oxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:18
L2	51	(eva near2 tois suvi near2 haukka marko near2 tuominen).in. and (ald or ale or atomic near2 layer near2 (process\$4 or deposit\$4 or epitax\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:18
S57	55	(hemispherical near2 grain) near10 substrate same oxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:21

S8	337	S1 same (oxide and (multi\$1compon\$6 or multi\$1layer or combinat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:21
L7	3	L5 same (oxide near2 tertiary)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:21
L6	457	L5 same (oxide and (multi\$1compon\$6 or multi\$1layer or combinat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:21
L5	11116	ald or atomic near2 layer near2 (epitax\$5 or deposit\$5) or ale	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:21
L4	60	(hemispherical near2 grain) near10 substrate same oxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:21
S51	69	("hfcl.sub.4" or hafnium near2 tetrachloride) near10 (hafnium near2 oxide or "hfo.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:22
S30	24	((ald or atomic near2 layer near2 (epitax\$5 or deposit\$5) or ale) near20 ("sio.sub.2" or sio2 or silicon near2 oxide)) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:22
L8	24	((ald or atomic near2 layer near2 (epitax\$5 or deposit\$5) or ale) near20 ("sio.sub.2" or sio2 or silicon near2 oxide)) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/17 12:22